



Attorney Docket No. Patent 81329A

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re the application of: JOSEPH J. DANKO

Serial No: 09/579,593

Group Art Unit: 2877

Filed: May 26, 2000

Examiner: G. J. Stock, Jr.

For: METHOD AND APPARATUS FOR INSPECTING A PATTERNED SEMICONDUCTOR WAFER

Mail Stop Fee Amendment  
Commissioner for Patents  
P.O. Box 1450  
Alexandria, Va 22313-1450

Dear Sir:

AMENDMENT

This communication is in response to an Office Action received on this application dated January 30, 2003. It is respectfully requested that the above-identified application be amended as follows:

IN THE CLAIMS:

Please amend claims 1-3, 4, 5, 11, 15, 18 and 19 as follows:

B1 1. (Twice Amended) An apparatus for detecting the presence of contaminant particles on a surface of a semiconductor wafer having repetitive patterns, said apparatus comprising:

- (a) means for producing a first beam of light and a second beam of light,
- (b) first optical means for illuminating a first region area on the semiconductor wafer with said first beam of light,

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